

PATENT ABSTRACTS OF JAPAN

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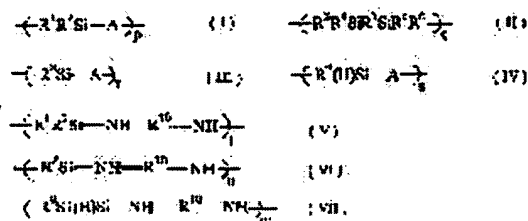
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(54) SILICON-CONTAINING COPOLYMER AND METHOD FOR PRODUCING THE SAME

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a polymer having high resistance, high light transmittance, a low dielectric constant, high mechanical strength and flexibility even by curing in air.

SOLUTION: This silicon-containing has 500-1,000,000 number-average molecular weight, contains an Si-O bond and comprises at least structural units represented by general formula (I) and general formula (II) and, if necessary, general formula (III)-(VII) (R1 to R6 and R8 and R9 are each independently an alkyl group, an alkenyl group, a cycloalkyl group, an aryl group, an aralkyl group, an alkylamino group, an alkylsilyl group or an alkoxy group; R7 is a bifunctional group; R10 is a bifunctional aromatic group; A is NH or O).



LEGAL STATUS

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